

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. AMAT/6437/ETCH/METAL/J81	Serial No. 10/092,456
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant Hwang, et al.	Confirmation No. 1212
(Use several sheets if necessary)		Filing Date March 6, 2002	Group 2818
Examiner Dung Anh Le			

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A1						
	A2						
	A3						
	A4						
	A5						

Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B1						<input type="checkbox"/>	<input type="checkbox"/>
	B2						<input type="checkbox"/>	<input type="checkbox"/>
	B3						<input type="checkbox"/>	<input type="checkbox"/>
	B4						<input type="checkbox"/>	<input type="checkbox"/>
	B5						<input type="checkbox"/>	<input type="checkbox"/>

OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
Dle	C1	Jung, K.B., et al., "Long term stability of dry etched magnetoresistive random access memory elements", <i>Journal of Vacuum Science and Technology: Part A</i> ; American Institute of Physics, New York, U.S., Vol. 18, No. 1, January 2000 (2000-01), pp. 268-272, XP001145970, ISSN: 0734-2101.
Dle	C2	van Delft, F.C.M.J.M., et al., "The etch mechanisms of magnetic materials in an HCl plasma", Fusion Technology and Plasmas Session of the Twelfth International Vacuum Congress (IVC-12) and Eighth International Conference on Solid Surfaces (ICSS-8), The Hague, Netherlands, 12-16 Oct. 1992, Vol. 200, No. 3, pp. 366-370, XP008022404, <i>Journal of Nuclear Materials</i> , May 1993, Netherlands, ISSN: 0022-3115.
Dle	C3	Cho, H. et al., "Inductively coupled plasma etching of CoFeB, CoZr, CoSm and FeMn thin films in interhalogen mixtures", <i>Materials Science and Engineering B (Solid-State Materials for Advanced Technology)</i> , 15 June 1999, Elsevier, Switzerland, Vol. B60, No. 2, pp. 107-111, XP004175032, ISSN: 0921-5107.

Examiner Dle	Date Considered April - 2004
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.